Author Index to Volume 9

Aberth, W.: The Wien filter and its application in chemistry, 383
Adams, F.: See Vertes, A.
Adams, J.: Charge-remote fragmentations: Analytical applications and fundamental studies, 141
Arpino, Patrick: Combined liquid chromatography mass spectrometry. Part II. Techniques and mechanisms of thermospray, 631
Bowie, J.H.: The fragmentations of even-electronic organic negative ions, 349
Budzikiewicz, H.: Selected reviews on mass spectrometric topics, 133, 259, 381, 499, 575, 671
Bursey, Maurice M.: Editorial, 501
Bursey, Maurice M.: Comments to readers: On acids and bases, 503
Bursey, Maurice M.: Change inversion of negative ions in tandem instruments, 555
Chang, T.-L.: Advances in organic mass spectrometry in China, 265
Crain, Pamela F.: Mass spectrometric techniques in nucleic acid research, 505
Dass, C.: Pericyclic reactions of radical cations, 1
De Laeter, J.R.: Mass spectrometry in cosmochemistry, 453
Fenn, J.B.: Electrospray ionization—principles and practice, 37
Gijbels, R.: See Vertes A.
Harrison, W.W.: See King, F.L.
King, F.L.: Glow discharge mass spectrometry: An introduction to the technique and its utility, 285
Kuck, D.: Mass spectrometry of alkyl benzenes and related compounds. Part I. Gas-phase ion chemistry of alkylbenzene radical cations, 187
Kuck, Dietmar: Mass spectrometry of alkylbenzenes and related compounds. Part II. Gas phase ion chemistry of protonated alkylbenzenes (alkylbenzenium ions), 583
Mann, M.: See Fenn, J.B.
Meng, C.K.: See Fenn, J.B.
Mikaya, A.I.: Reaction gas chromatography/mass spectrometry, 115
Miller, J.M.: Fast atom bombardment mass spectrometry (FAB MS) of organometallic, coordination, and related compounds, 319
Mirza, U.A.: See Vairamani, M.
Russell, D.H.: See Tecklenburg, R.E., Jr.
Srinivas, R.: See Vairamani, M.
Tecklenburg, R.E., Jr.: An evaluation of the analytical utility of the photodissociation of fast ion beams, 405
Vairamani, M.: Unusual positive ion reagents in chemical ionization mass spectrometry, 235
Vertes, A.: Diagnostics and modeling of plasma processes in ion sources, 71
Wang, G.-H.: See Chang, T.-L.
Whitehouse, C.M.: See Fenn, J.B.
Wollnik, H.: See Aberth, W.
Wong, S.F.: See Fenn, J.B.
Zaikin, V.G.: See Mikaya, A.I.